

ABSTRACT OF THE DISCLOSURE

METHOD, APPARATUS, AND SYSTEM FOR DETERMINING OPTIMUM OPERATION

RECIPE FOR OPTICAL FILM-THICKNESS MEASURING DEVICE

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A method of automatically determining optimum recipe parameters constituting an operation recipe of an optical film-thickness measuring device within a short period of time is disclosed. The method includes storing in a memory a plurality of parameter sets each including a plurality of recipe parameters constituting an operation recipe; performing
10 simulation of change in film thickness with polishing time with use of the plurality of parameter sets and data of reference spectra of reflected light from a polished substrate, the reference spectra being stored in a data server; inputting at least one index value for evaluating a manner of the change in film thickness into an evaluation calculation formula to calculate a plurality of comprehensive evaluation values for the plurality of parameter sets;
15 and selecting an optimum one of the plurality of parameter sets based on the plurality of comprehensive evaluation values.

FIG. 22